4 - 22 A Charge Sensitive Spectroscopy Amplifier for Position Sensitive Micro-channel Plate Detectors

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Position sensitive Micro-Channel Plate (MCP) detectors are widely used for detection of particles like electrons and ions^[1]. A previous work shows that integrating the electronics into an MCP detector is an optimal noise reduction method^[2]. In this paper, we present a compact, low noise charge sensitive spectroscopy amplifier which could be integrated into MCP detectors for charge divide readout schemes.

A logic diagram of the spectroscopy amplifier is shown in Fig. 1. It is composed of a charge sensitive preamplifier (PA), a pulse shaper (PS) and a liner amplifier (LA). The PS is implemented with a four stage Bessel low pass active filter in a Sallen-Key topology^[3].

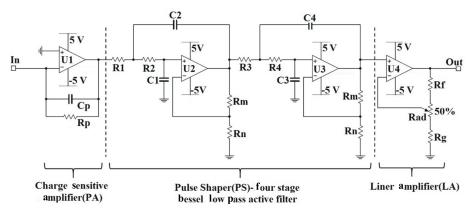


Fig. 1 Logic diagram of the spectroscopy amplifier. It is composed of a charge sensitive preamplifier, a pulse shaper implemented with a 4th stage Bessel low pass active filter, and a liner amplifier.

Fig. 2 shows the layout of the spectroscopy amplifier, which combines the PA, the PS and the LA in a four layer printed circuit board (PCB) with a size of 42 mm×44 mm. We reserve some parallel resistors on the board for adjusting the time constant τ p and the poles and zeros of the PS.

The amplifier is tested by a chevron configured MCP detector with a parallel strips resistive anode^[4] which irradiated by a 241 Am α -source in vacuum. Fig. 3 shows a typical amplified pulse produced by MCP. The amplitude, shaping time and full width of the output are about 1.2 V, 700 ns and 3 μ s respectively.

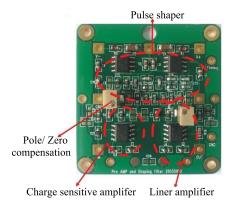


Fig. 2 (color online) A photograph of the spectroscopy amplifier within a PCB of a size of 42 mm \times 44 mm.

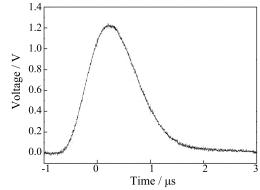


Fig. 3 An MCP pulse amplified and shaped by the spectroscopy amplifier. The detector was irradiated by a 241 Am α -source. Obtained with a 1 GHz Tektronix OPO5104 oscilloscope.

References

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